

ABSTRACT OF THE DISCLOSURE

PROCESSING SYSTEM, PROCESSING METHOD, MEASUREMENT
APPARATUS, SUBSTRATE PROCESSING APPARATUS AND ARTICLE
MANUFACTURING METHOD

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The present invention provides a processing system that includes a first apparatus and a second apparatus, and processes a substrate, wherein the first apparatus includes a first measurement unit configured to detect a first structure and a second structure different from the first structure provided on the substrate, and measure a relative position between the first structure and the second structure, and the second apparatus includes an obtainment unit configured to obtain the relative position measured by the first measurement unit, a second measurement unit configured to detect the second structure and measure a position of the second structure, and a control unit configured to obtain a position of the first structure based on the relative position obtained by the obtainment unit and the position of the second structure measured by the second measurement unit.

(Figure 9)